Supporting information

Preparation of Chiral Mesoporous Materials with Helicity Perfectly Controlled

Toshiyuki Yokoi,[†] Kyohei Ogawa,[†] Daling Lu,[†] Junko N. Kondo,[†] Yoshihiro Kubota,[‡] and Takashi Tatsumi^{*, †}

[†]Chemical Resources Laboratory, Tokyo Institute of Technology, Nagatsuta 4259, Midori-ku, Yokohama 226-8503 Japan

[‡]Division of Materials Science and Chemical Engineering, Graduate school of Engineering, Yokohama National University, 79-5 Tokiwadai, Hodogaya-ku, Yokohama 240-8501, Japan

Tel.: +81-45-924-5238. Fax: +81-45-924-5282. E-mail: ttatsumi@cat.res.titech.ac.jp



Figure S1 SEM image of the surfactant-extracted 100 % right-handed chiral mesoporous organosilica.



Figure S2

TEM images of the surfactant-extracted 100 % right-handed chiral mesoporous organosilica with different rotation angles along the axe.



Figure S3 XRD pattern of the surfactant-extracted 100 % right-handed chiral mesoporous organosilica.



Figures S4 (a) and (b)

(a) N_2 adsorption - desorption isotherms of the surfactant-extracted 100 % right-handed chiral mesoporous organosilica after the extraction and (b) corresponding pore size distribution by the BJH method using adsorption branch.



Figures $\overline{S5}$ (a) and (b)

(a) XRD patterns and (b) SEM images of the surfactant-extracted 100% right-handed CMOS products synthesized with the temperature varied ranging from 25 to 100 °C.



Figure S6 SEM images of the surfactant-extracted 100 % left-handed chiral mesoporous organosilica.



Figures S7 (a) and (b) (a) Solid-state ²⁹Si MAS NMR spectrum and (b) XRD pattern of the calcined product.



Figures S8 (a) and (b)

H₂O adsorption - desorption isotherms of the 100% right-handed (a) CMOS and (b) CMS samples.



Figures S9 (a) and (b)

Typical SEM images of the surfactant-extracted products synthesized with the combinations of (a) C_{14-L} -AlaA / D-arginine and (b) C_{14-D} -AlaA / L-arginine.